L	Hits	Search Text	DB	Time stamp
Number				
1	626	("low k" or "methyl doped silica" or	USPAT;	2003/06/02
		"fluorinated silicon glass" or FSG) and	EPO; JPO;	15:12
		(PECVD or "plasma enhanced chemical vapor	IBM TDB	
		deposition")	_	
2	86	(("low k" or "methyl doped silica" or	USPAT;	2003/06/02
		"fluorinated silicon glass" or FSG) and	EPO; JPO;	13:38
		(PECVD or "plasma enhanced chemical vapor	IBM TDB	
		deposition") ) and power and ("methyl	_	
		silane" or ("nitrous oxide" or		
_	_	"NO.sub.2"))		
3	1		USPAT	2003/06/02
	4.00			13:21
6	107	(("low k" or "methyl doped silica" or	USPAT;	2003/06/02
·		"fluorinated silicon glass" or FSG) and	EPO; JPO;	15:12
		(PECVD or "plasma enhanced chemical vapor	IBM_TDB	
		deposition") ) and ("methyl silane" or		
7	201	("nitrous oxide" or "NO.sub.2"))		
′	391	("low k" or "methyl doped silica" or	USPAT;	2003/06/02
		"fluorinated silicon glass" or FSG) and	EPO; JPO;	13:52
		(PECVD or "plasma enhanced chemical vapor	IBM_TDB	
12	89	deposition") and power		
12	09	(("black diamond" or "methyl doped	USPAT;	2003/06/02
		silica" or "low k") and (PECVD or "plasma	EPO; JPO;	15:05
l		enhanced chemical vapor deposition") )	IBM_TDB	
		<pre>and ("methyl silane" or ("nitrous oxide" or "NO.sub.2"))</pre>		
13.	37	(("black diamond" or "methyl doped		
	. 37	silica" or "low k") and (PECVD or "plasma	USPAT;	2003/06/02
		enhanced chemical vapor deposition") )	EPO; JPO;	15:06
		and "methyl silane"	IBM_TDB	
11 ~	506	("black diamond" or "methyl doped silica"	HCDATE.	2002/06/22
		or "low k") and (PECVD or "plasma	USPAT; EPO; JPO;	2003/06/02
		enhanced chemical vapor deposition")	IBM TDB	16:08
14	20	"low k" and "methyl silane" and	USPAT;	2003/06/02
		("nitrous oxide" or "NO.sub.2") and	EPO; JPO;	15:14
		(helium or He) and (oxygen or	IBM TDB	13.14
		"O.sub.2") and power	1011_100	
15	1	, · · <u>·</u> · · · · ·	USPAT	2003/06/02
				16:04
16	28	"black diamond" and (PECVD or "plasma	USPAT;	2003/06/02
		enhanced chemical vapor deposition")	EPO; JPO;	16:23
	l		IBM TDB	10.23
17	65	("black diamond" or "methyl doped	USPAT;	2003/06/02
		silica") and (CVD or " chemical vapor	EPO; JPO;	16:24
		deposition")	IBM TDB	